

P27374.A08

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

*Please
Enter
LP @ 1/10/06*

Applicants	: Dureseti CHIDAMBARRAO, et al.	Group Art Unit: 2814
Appl. No.	: 10/605,108	Examiner: PHAM, Long
Filed	: September 9, 2003	Confirmation No. 2107
For	: METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI ON SI/GE SUBSTRATE	

RESPONSE UNDER 37 C.F.R. 1.116

Commissioner for Patents
U.S. Patent and Trademark Office
Customer Window, Mail Stop AF
Randolph Building
401 Dulany Street
Alexandria, VA 22314
Sir:

Responsive to the Final Official Action of June 8, 2006, reconsideration and withdrawal of the rejections made therein are respectfully requested, in view of the following remarks.

A listing of the claims begin on page 2; and

Remarks begin on page 7.

Inasmuch as the Official Action sets a three-month shortened statutory period which expires September 8, 2006, this Amendment is being timely filed and no extension of time is believed necessary. However, if an extension is deemed by the Patent and Trademark Office to be necessary, the same is hereby requested and the Patent and Trademark Office is hereby authorized to charge any necessary fees in connection therewith or any fees necessary to preserve the pendency of this application to deposit account No. 09-0458.